REMARKS

Attached hereto is a marked-up version of the changes made to the specification and claims by the current amendment. The attached page(s) is captioned "**Version With Markings To Show Changes Made**."

Respectfully submitted,

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VERSION WITH MARKINGS TO SHOW CHANGES MADE

IN THE SPECIFICATION

Page 1, before the first line, please insert as a separate paragraph:

This application is the US national phase of international application PCT/GB00/03602 filed 20 September 2000, which designated the US.

IN THE CLAIMS

7. A method of fabricating a porous filter element according to ~~any one of the preceding~~ claim~~s~~ 1, wherein the regions extend in a straight line from a first side of said photosensitive material to a second, opposite side of said material.

8. A method of fabricating a porous filter element according to ~~any one of the preceding~~ claim~~s~~ 1, wherein the step of treating the exposed photosensitive material to selectively remove regions thereof comprises removing regions having an exposure below a predetermined level.

9. A method of fabricating a porous filter element according to ~~any one of the preceding~~ claim~~s~~ 1, wherein the step of treating the exposed photosensitive material to selectively remove regions thereof comprises removing regions having an exposure above a predetermined level.

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10. A method of fabricating a porous filter element according to ~~any one of the preceding~~ claims 1, wherein the pattern is substantially non-varying through the depth of the material whereby said regions have a constant cross-section through the material.

11. A method of fabricating a porous filter element according to ~~any one of~~ claims ~~1 to 9~~, wherein the pattern varies through the depth of the material to vary the cross-section of said regions through the depth of the material.

12. A method of fabricating a porous filter element according to claim 10 ~~or 11~~, wherein the pattern repeats across the material perpendicular to the depth direction to create in the material a regular array of identical regions which extend through the depth of the material.

13. A method of fabricating a porous filter element according to ~~any one of the preceding~~ claims 1, wherein the material is a mixture of an epoxy resin and a photoacid generator.

14. A method of fabricating a porous filter element according to ~~any one of the preceding~~ claims 1, wherein the material to be exposed is in the form of a thin film.

15. A method of fabricating a porous filter element according to ~~any one of the preceding~~ claims 1 wherein the photosensitive material comprises a plurality of regions of different composition such that the different regions react differently to exposure followed by treatment.

17. A method of fabricating a porous filter element according to ~~any one of the preceding~~ claims 1, comprising the further step of using said treated material as a lost mould to form a porous filter element.

20. A method according to ~~any one of the preceding~~ claims 1 wherein the exposure time and/or intensity of the e.m. radiation is set selectively in accordance with the desired size of the regions.

21. A porous filter element made by the method of ~~any one of the preceding~~ claims 1.